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APPLICATION NO). I	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/517,314		03/02/2000	Chih-Chen Cho	M4065.0223/P223	5039
24998	7590	07/14/2003			
DICKSTEIN SHAPIRO MORIN & OSHINSKY LLP				EXAMINER	
2101 L STREET NW WASHINGTON, DC 20037-1526				KANG, DONGHEE	
				ART UNIT ·	PAPER NUMBER
		ç:	7	2811	
	,		4	DATE MAILED: 07/14/2003	

Please find below and/or attached an Office communication concerning this application or proceeding.

Advisory Action BEST AVAIL

Application No.	Applicant(s)	
09/517,314	CHO, CHIH-CHEN	
Examiner	Art Unit	
Donghee Kang	2811	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

THE REPLY FILED 17 June 2003 FAILS TO PLACE THIS APPLICATION IN CONDITION FOR ALLOWANCE. Therefore, further action by the applicant is required to avoid abandonment of this application. A proper reply to a final rejection under 37 CFR 1.113 may only be either: (1) a timely filed amendment which places the application in condition for allowance; (2) a timely filed Notice of Appeal (with appeal fee); or (3) a timely filed Request for Continued Examination (RCE) in compliance with 37 CFR 1.114.

Application/Control Number: 09/517,314

Art Unit: 2811



DETAILED ACTION

Response to Arguments

1. Applicant argues that there is no motivation to combine the two figures since they are directed to providing alternate embodiments employing different interconnect materials. This is not convincing because it is conventional to use copper (Cu) layer with barrier layer as a conductive interconnection layer instead of aluminum (Al) because copper has a lower resistivity than aluminum hence providing a higher speed. Chiang also teaches in alternate embodiment using copper layer instead of aluminum layer.

Therefore, it would have been obvious to one of ordinary skill in the art at the time the invention was made to substitute the aluminum with copper/barrier layer since the copper layer provides higher speed than aluminum hence to obtain higher density in ICs.

2. Applicant argues that there is no motivation to combine Chiang's Fig.11 with Fig.9 since a wider interconnect would result. This is incorrect. Since copper layer has a lower resistive than aluminum layer, the line width of the cooper interconnection of Fig.11 is smaller than the line width of the aluminum interconnection. Therefore, it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify the Fig.11 of Chiang by replacing the aluminum interconnection with copper/barrier interconnection in order to provide smaller interconnection because copper layer has a lower resistive than aluminum layer.

Application/Control Number: 09/517,314

Art Unit: 2811

DEST AVAILABLE CUPY

3. Applicant argues that the combination of Chiang and Matsuura is improper because there is no motivation to have a first and second etched via over a single conductive plug.

In response to applicant's argument that there is no suggestion to combine the references, the examiner recognizes that obviousness can only be established by combining or modifying the teachings of the prior art to produce the claimed invention where there is some teaching, suggestion, or motivation to do so found either in the references themselves or in the knowledge generally available to one of ordinary skill in the art. See *In re Fine*, 837 F.2d 1071, 5 USPQ2d 1596 (Fed. Cir. 1988) and *In re Jones*, 958 F.2d 347, 21 USPQ2d 1941 (Fed. Cir. 1992). In this case, forming a double (first and second) etched via is generally known in the art and also taught by Matsuura (see Fig.1) forming first and second etch via (7) in his device to reduce height.

Therefore, it would have been obvious to one of ordinary skill in the art at the time the invention was made to incorporate the double etched via of Matsuura into the Chiang's device since it can reduce a height of the ICs so as to form several interconnection layer without increasing a volume.

4. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Donghee Kang whose telephone number is 703-305-9147. The examiner can normally be reached on Monday through Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Tom Thomas can be reached on 703-308-2772. The fax phone numbers

Application/Control Number: 09/517,314

Art Unit: 2811

DEST AVAILABLE CUPY

for the organization where this application or proceeding is assigned are 703-308-7722 for regular communications and 703-308-7722 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

TOM THOMAS

SUPERVISORY PATENT EXAMINER TECHNOLOGY CENTER 2800

dhk July 11, 2003